

EAST Search History

Ref #	Hits	Search Query	DBs	Default Operator	Plurals	Time Stamp
L2	6	(("6536452") or ("6613692") or ("6514073") or ("6634806") or ("6888020") or ("6513537")).PN.	US-PGPUB; USPAT; USOCR	OR	OFF	2007/12/01 15:58
L3	130	(substrate or wafer or semiconductor) and (chuck near2 mov\$3 near2 up adj2 down)	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT	OR	ON	2007/12/01 15:59
L4	31	distance adj between adj wafer adj3 chuck	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT	OR	ON	2007/12/01 16:00
L5	3	4 with (mov\$3 or retreat\$3)	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT	OR	ON	2007/12/01 16:00
L6	2	(substrate or wafer or semiconductor) same (chuck or susceptor or holder) with metal with hydrophobic	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT	OR	ON	2007/12/01 16:02
L7	2	((substrate or wafer or semiconductor) same (chuck or susceptor or holder)) with metal with hydrophobic	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT	OR	ON	2007/12/01 16:02
L8	2	(substrate or wafer or semiconductor) same ((chuck or susceptor or holder) with metal with hydrophobic)	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT	OR	ON	2007/12/01 16:03
L9	44	(substrate or wafer or semiconductor) and ((chuck or susceptor or holder) with metal with teflon)	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT	OR	ON	2007/12/01 16:11
L10	35	(substrate or wafer or semiconductor) and ((chuck or susceptor or holder) with metal with teflon) and (clean\$4 or etch\$4 or rins\$4)	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT	OR	ON	2007/12/01 16:13
L11	0	(substrate or wafer or semiconductor) and ((chuck or susceptor or holder) with (metal near3 ((coat or layer\$3) near2 teflon))) and (clean\$4 or etch\$4 or rins\$4)	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT	OR	ON	2007/12/01 16:15

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L12	0	(substrate or wafer or semiconductor) and ((chuck or susceptor or holder or member) with (metal near3 ((coat or layer\$3) near2 teflon))) and (clean\$4 or etch\$4 or rins\$4)	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT	OR	ON	2007/12/01 16:15
L13	1	(substrate or wafer or semiconductor) and ((chuck or susceptor or holder or member) same (metal near3 ((coat or layer\$3) near2 teflon))) and (clean\$4 or etch\$4 or rins\$4)	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT	OR	ON	2007/12/01 16:31